

L Number	Hits	Search Text	DB	Time stamp
19	568	((micromach\$6 microelect\$6 "MEMS") near6 (sense\$5 detect\$4 transducer cell gage gauge indicat\$5 identif\$5 measur\$5 determina\$5 measur\$5)).clm.	USPAT; US-PGPUB; EPO; JPO	2004/04/05 10:58
20	5	((micromach\$6 microelect\$6 "MEMS") near6 (sense\$5 detect\$4 transducer cell gage gauge indicat\$5 identif\$5 measur\$5 determina\$5 measur\$5)).clm.) and ((ultra\$6 extrem\$6 very high (over near3 ("5000" "6000" "10,000")))) near3 (pressure psi)).clm.	USPAT; US-PGPUB; EPO; JPO	2004/04/05 11:01
21	55090	(pressure near4 (sens\$4 detect\$4 gauge transducer measur\$4 indicat\$4 identif\$4 monitor\$4 determina\$4 calculat\$5)).clm.	USPAT; US-PGPUB; EPO; JPO	2004/04/05-10:59
22	14179	((pressure near4 (sens\$4 detect\$4 gauge transducer measur\$4 indicat\$4 identif\$4 monitor\$4 determina\$4 calculat\$5)).clm.) and (diaphragm elastic\$5 resilien\$5 flex\$5 bend\$5 rubber deform\$5 membrane).clm.	USPAT; US-PGPUB; EPO; JPO	2004/04/05 11:01
23	982	((pressure near4 (sens\$4 detect\$4 gauge transducer measur\$4 indicat\$4 identif\$4 monitor\$4 determina\$4 calculat\$5)).clm.) and (diaphragm elastic\$5 resilien\$5 flex\$5 bend\$5 rubber deform\$5 membrane).clm.) and ((ultra\$6 extrem\$6 very high (over near3 ("5000" "6000" "10,000")))) near3 (pressure psi)).clm.	USPAT; US-PGPUB; EPO; JPO	2004/04/05 11:01
24	86	((pressure near4 (sens\$4 detect\$4 gauge transducer measur\$4 indicat\$4 identif\$4 monitor\$4 determina\$4 calculat\$5)).clm.) and (diaphragm elastic\$5 resilien\$5 flex\$5 bend\$5 rubber deform\$5 membrane).clm.) and ((ultra\$6 extrem\$6 very high (over near3 ("5000" "6000" "10,000")))) near3 (pressure psi)).clm.) and substrate	USPAT; US-PGPUB; EPO; JPO	2004/04/05 11:02
25	41	((pressure near4 (sens\$4 detect\$4 gauge transducer measur\$4 indicat\$4 identif\$4 monitor\$4 determina\$4 calculat\$5)).clm.) and (diaphragm elastic\$5 resilien\$5 flex\$5 bend\$5 rubber deform\$5 membrane).clm.) and ((ultra\$6 extrem\$6 very high (over near3 ("5000" "6000" "10,000")))) near3 (pressure psi)).clm.) and substrate.clm.	USPAT; US-PGPUB; EPO; JPO	2004/04/05 11:02